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IWJT 2027

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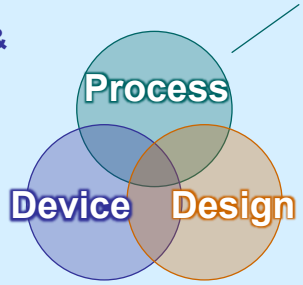
24th International Workshop on Junction Technology

2027/6/17(Thu.)-18(Fri.),
Ryukoku University, Fukakusa Campus Jojukan Japan

The International Workshop on Junction Technology (IWJT), established in 2000, began as a premier forum on shallow junction formation technologies for silicon semiconductor devices. While maintaining its core focus on junction technologies, IWJT has expanded to encompass silicon and compound semiconductor devices, advanced CMOS, memory, image sensor, optoelectronic and power devices, as well as enabling technologies such as doping, 2D materials, and 3D integration. Following its 25th anniversary in 2025 and expansion to Europe in 2026, IWJT continues to bring together researchers and engineers from academia and industry to discuss future semiconductor technologies.

Scopes

- Power Conversion & Energy Devices
- Advanced CMOS
- Memory Devices
- Image Sensors
- Optoelectronic Devices



- Annealing
- Doping (Epi. & Implantation)
- Advanced Equipment
- Engineered Substrates
- 3D Integration
- 2D Materials

- Characterization
- Modeling
- Simulation

Best Paper Award and Young Award (under 35 age on the workshop day) will be selected. Detail can be seen in the conference website.

Committees

General Chair : Satoshi Shibata (Panasonic Operational Excellence Co., Ltd.)
Executive Chair : Osamu Nakatsuka (Nagoya University)
Program Chair : Yoshiaki Kikuchi (National Institute for Materials Science)

Conference Website https://smartconf.jp/content/iwjt2027/

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